

## PATENT ABSTRACTS OF JAPAN

(11)Publication number : 07-007052

(43)Date of publication of application : 10.01.1995

(51)Int.Cl.

H01L 21/66

(21)Application number : 05-145210

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(22)Date of filing : 16.06.1993

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### (54) ELECTRIC PROPERTIES MEASUREMENT PROBE

#### (57)Abstract:

**PURPOSE:** To provide excellent positional accuracy and flatness and high mechanical strength of a contactor and hence enhance the measurement durability and reliability of the contactor by obtaining an electric properties measurement probe having contactors as a fine array pitch since this probe is manufactured based on such a process as photolithograph and thin film formation.

**CONSTITUTION:** This is designed based on a cantilever beam structure 15 which comprises single crystal silicon, silicon oxide and nitriding silicon and polysilicon or at least one metal layer. A continuity metal film 14 is formed on the surface. This cantilever beam structure 15 is held by an insulation board 18 which forms a continuity wiring pattern 19, thereby using this as an electric properties measurement probe.

